

SEP 26 2006

SHEET 1 OF 1

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10/580,833

LIST OF REFERENCES CITED BY APPLICANT

APPLICANT

Kazuhito YASUDA, et al.

FILING DATE

May 26, 2006

GROUP

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						
	AM						
	AN						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION	
					YES	NO
	AO					
	AP					
	AQ					
	AR					
	AS					

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)

/MG/	AT	NAKANISHI, Yutaro et al., "Growth and Electronic Properties of Thick CdTe Layers Grown on GaAs by MOVPE", Technical Report of IEICE., Vol. 103, No. 50, pgs. 81-85, 2003.				
/MG/	AU	MASUDA, Yusuke et al., "Arsenic Doping In CdTe Layers Grown by Metalorganic Vapor Phase Epitaxy", Technical Report of IEICE., Vol. 101, No. 82, pgs. 13-18, 2001.				
/MG/	AV	YASUDA, K. et al., "MOVPE growth of (100) CdZnTe Layers Using DiPZn", Journal of Crystal Growth, Vol. 159, pgs. 121-125, 1996.				
/MG/	AW	UCHIDA, Kei et al., "Study on Detector for Detecting Large Images of Both CdTe- x Ray and Y Ray by Using MOVPE", Dai 64 Kai Extended Abstracts, the Japan Society of Applied Physics, No. 1, pg. 245, 2003 (With Partial English Translation)				
/MG/	AX	WANG, Wen-Sheng et al., "(100) or (111) Heteroepitaxy of CdTe Layers on (100) GaAs Substrates by Organometallic Vapor Phase Epitaxy", Materials Chemistry and Physics, Vol. 51, pgs. 178-181, 1997.				
/MG/	AY	LEO, G. et al., "Influence of a ZnTe Buffer Layer on the Structural Quality of CdTe Epilayers Grown on (100) GaAs by Metalorganic Vapor Phase Epitaxy", J.Vac.Technol.B., Vol. 14, No. 3, pgs 1739-1744, 1996.				
	AZ				<input type="checkbox"/> Additional References sheet(s) attached	

Examiner

/Mark Gaworecki/

Date Considered

07/14/2007

*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.